

Supporting Information

Enriched Oxygen Vacancies in SnO_{2-x} with Narrow Bandgap for Highly Sensitive Gas Sensing

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Experimentation

Characterization

Powder X-ray diffraction (PXRD) of samples were recorded on a Rigaku Smartlab MiniFlex 600 X-ray diffractometer using Cu $K\alpha$ radiation ($\lambda = 1.54178 \text{ \AA}$) at 30 kV and 15 mA. The pdf card of SnO_2 was derived from the Jade software. Scanning electron microscope (SEMZEISS-300) was operated at 3.0 kV. Transmission electron microscope (TEM) images were obtained on a JEOL-2010 transmission electron microscope at an acceleration voltage of 200 kV. X-ray photoelectron spectroscopy (XPS) data was collected on a Thermo Scientific ESCALAB 250 Xi XPS system. UV-visible absorption curve and transmittance data were collected on a Perkin–Elmer Lambda 950 spectrophotometer using BaSO_4 as a white standard, use the powder synthesized in the same bottom with SnO_{2-x} thin film.

Synthesis of SnO_{2-x} .

Glass substrates ($1 \times 3 \text{ cm}$) were cut and sequentially ultrasonically cleaned in ethanol and deionized water, followed by drying for later use. A solution (Solution A) was prepared by dissolving 357 mg KBr in 10 mL deionized water. Separately, 350.6 mg $\text{SnCl}_4 \cdot 5\text{H}_2\text{O}$ was dissolved in 60 mL glacial acetic acid to form Solution B. The two solutions were mixed thoroughly, followed by the addition of 10 mL anhydrous ethanol, and the mixture was ultrasonicated for 5 min. The resulting precursor solution was divided into ten 8 mL Teflon-lined autoclaves, with 0.0237 g (0.2 mmol) Sn powder added to each. Cleaned glass substrates were immersed in the solutions, leaning against the inner walls of the vessels. The autoclaves were sealed and heated at 200 °C for 12 h in an oven. Upon completion, SnO_{2-x} thin films were uniformly deposited on the substrates, with SnO_{2-x} powder samples also collected from the reaction mixture.

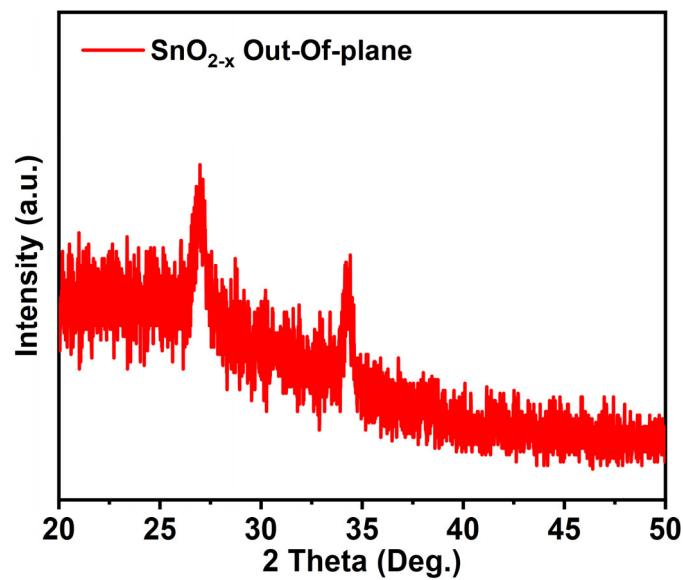


Fig. S1 Out-of-plane XRD pattern of SnO_{2-x} .

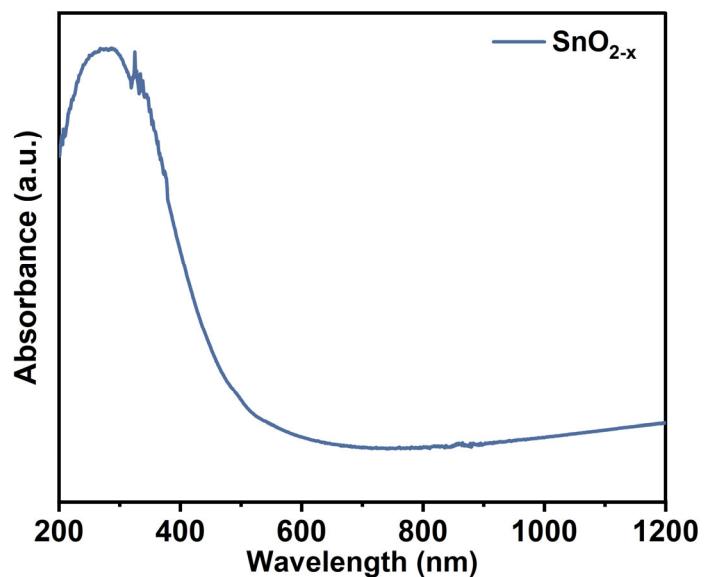


Fig. S2 Solid-state ultraviolet absorption spectroscopy of SnO_{2-x} .

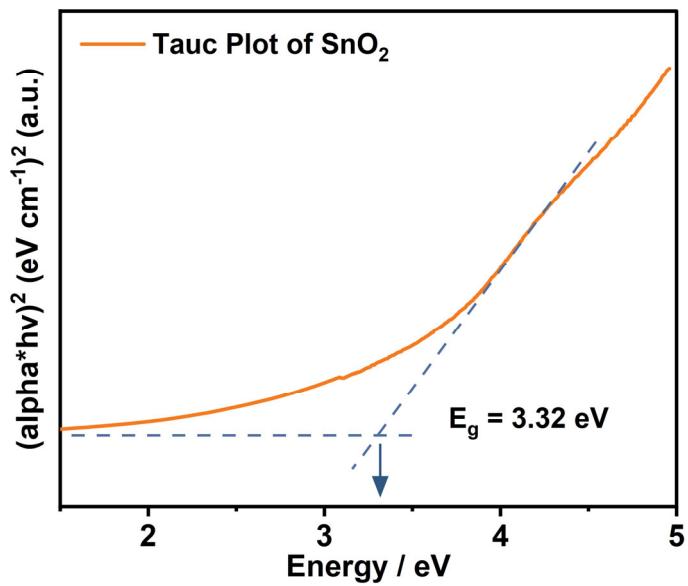


Fig. S3 Tauc plot of SnO_2 .

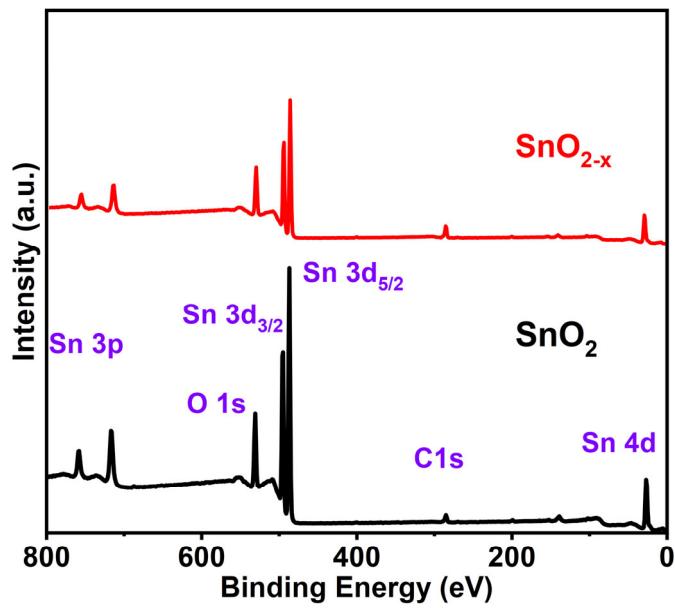


Fig. S4 XPS general spectrum of SnO_2 and SnO_{2-x} .

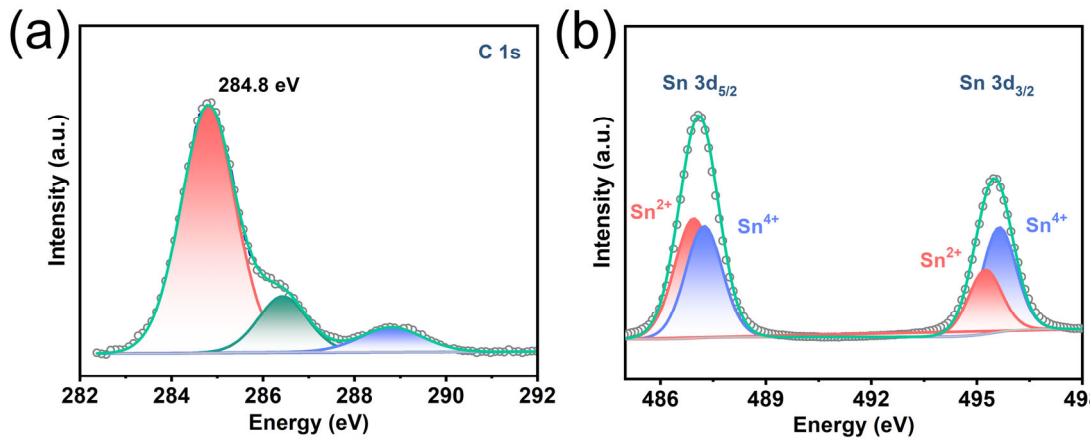


Fig. S5 XPS spectrum of C 1s and Sn 3d ($3d_{5/2}$ and $3d_{3/2}$) of SnO_{2-x} .

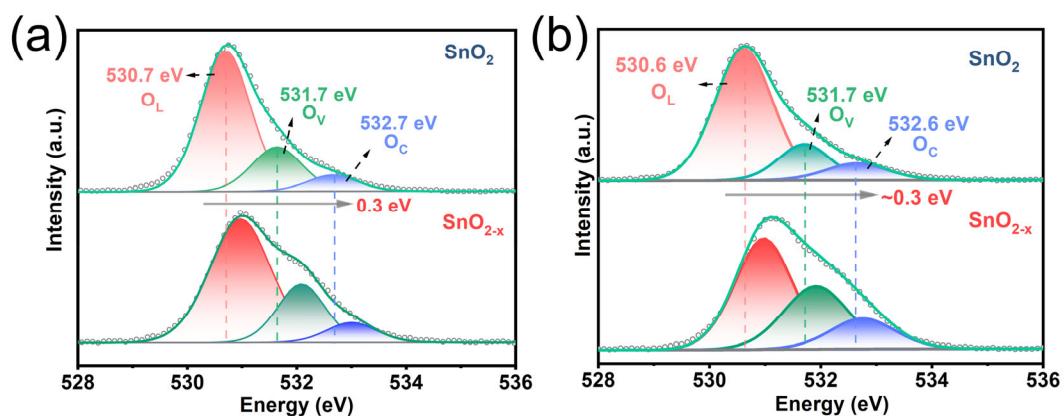


Fig. S6 XPS spectrum of O 1s for multiple sample comparisons.

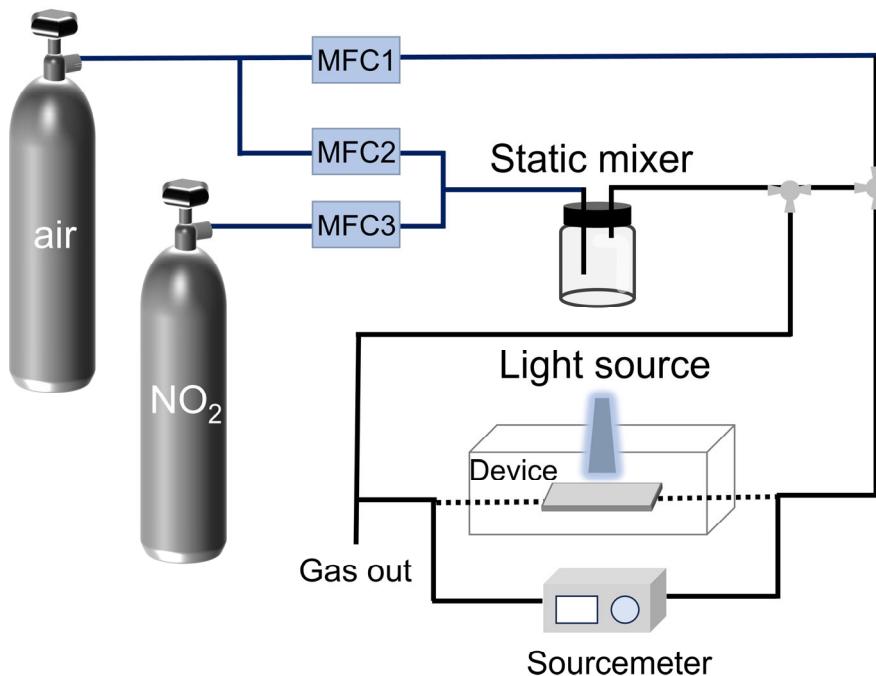


Fig. S7 Gas sensing system.

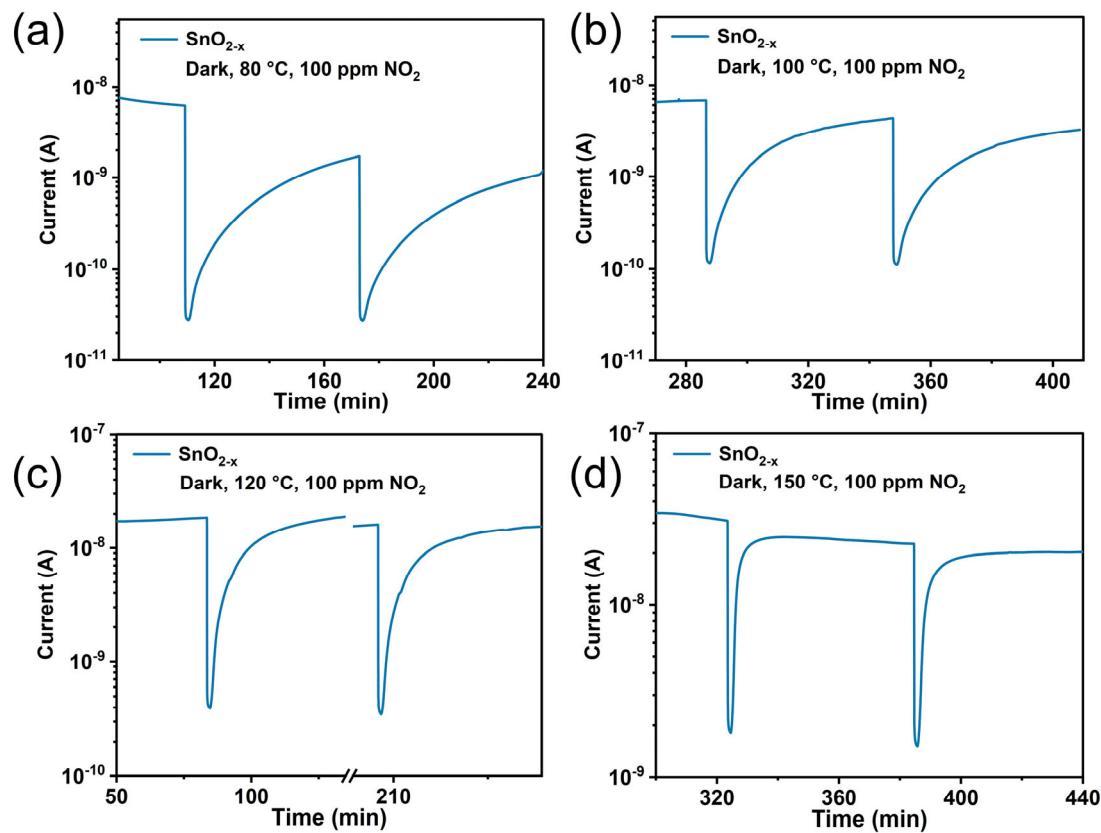


Fig. S8 Response curves to NO₂ under different temperatures.

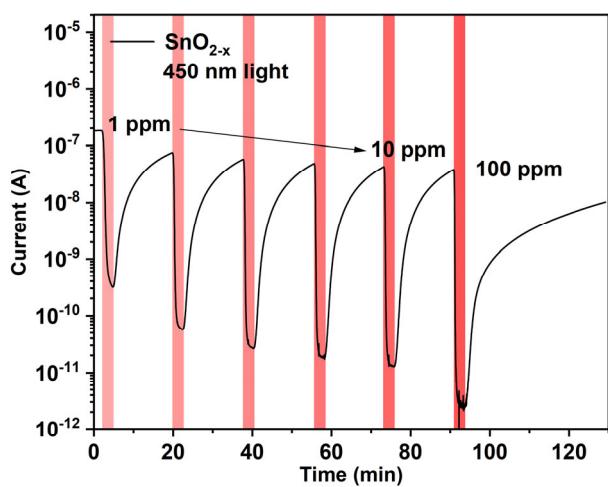


Fig. S9 Response-recovery curve with concentration of 1 - 100 ppm.

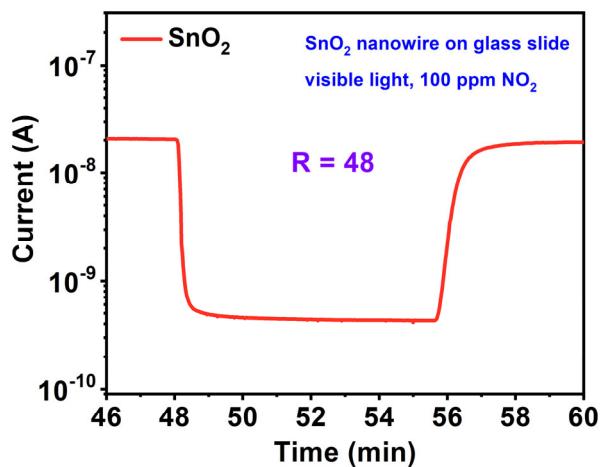


Fig. S10 Response of SnO_2 to 100 ppm NO_2 under visible light.

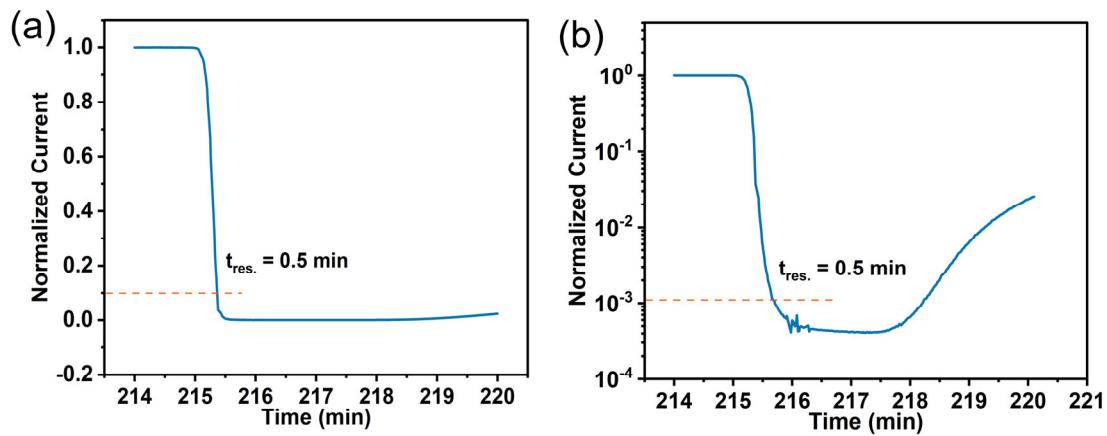


Fig. S11 Schematic of steady state on response to 10 ppm NO₂.

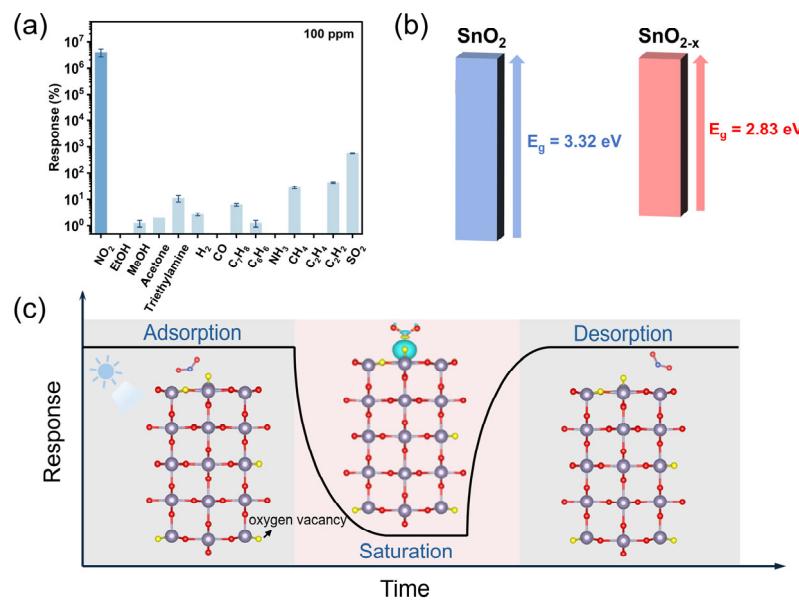


Fig. S12 (a) Responses comparison among NO₂ and interference gases of SnO_{2-x}. (b) Energy level between SnO₂ and SnO_{2-x}. (c) Conceptual diagram of mechanism of SnO_{2-x} to NO₂.

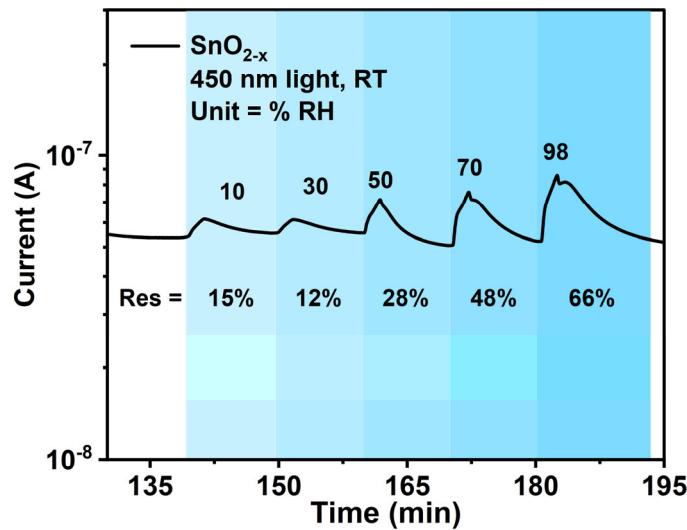


Fig. S13 Humidity sensing curve of SnO_{2-x} .

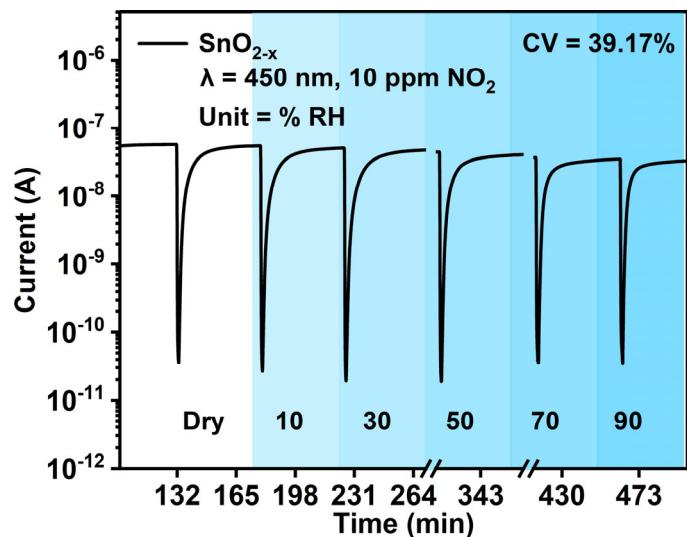


Fig. S14 Dynamic response curves of the SnO_{2-x} sensor exposed to 10 ppm NO_2 under different relative humidity levels (Dry, 10%, 30%, 50%, 70%, and 90% RH) at room temperature under 450 nm light illumination.

Table S1. Room-temperature NO₂ sensing performance of different sensor devices under visible or UV light activation.

Sensing materials	Light	LOD (ppb)	Res.%/Con. (ppm)	t _{res} /t _{rec} (min)	Ref.
SnO_{2-x}	Visible	0.006	2055300/100	0.5/120	This work
HOF-1	Vis.	8	170000/100	2.5/0.6	¹
SnO ₂ /ZnO	UV	--	619/5	1.5/3.7	²
ZnO	UV	--	410/20	3.7/2	³
TiO ₂ @COF	Vis.	1410	572/100	0.91/9.5	⁴
Au/ZnO	Vis.	—	60/5	25/ > 40	⁵
Au-SnO ₂	Vis.	6	17500/5	38.3/irr.	⁶
Cu ₃ (HHTP) ₂ /Fe ₂ O ₃	Vis.	11	89/5	~ 30/120	⁷
Zn-TDCOF-12	Vis.	7.9	54300/100	8.1/10.6	⁸
ZnO/SnO ₂	UV	--	10 ⁵ /0.5	7/8	⁹
Pt-ZnO@PDA-1.5 nm	Vis.	108	18489/100	0.37/-	¹⁰
In ₂ O ₃ nanowire array	Vis.	10	4.5/0.5	9/20	¹¹
3D TiO ₂	Vis.	0.2	370/5	7.1/16	¹²
TiO ₂ @NH ₂ -MIL-125	Vis.	1.1	207/10	0.28/1.3	¹³
ZnO	UV	--	120/20	15/48	¹⁴
Cu/Cu ₂ O	Vis.	--	527/10	0.5/-	¹⁵
SnO ₂ @SnS ₂	Vis.	1	520/0.2	15.8/19.3	¹⁶
ZnO/g-C ₃ N ₄	Vis.	38	4480/7	2.4/3.2	¹⁷
SnS ₂ /rGO	Vis.	5.03	650/1	1.3/4	¹⁸
SnS ₂ /TiO ₂	Vis.	1.7	40/1	0.72/1.7	¹⁹
SnS ₂	Vis.	38	1080/8	2.7/3.9	²⁰
TiO _{2-x} N _x	UV-vis	--	~14/10	~6/6	²¹
2D SnS ₂	Vis.	0.32	1430/5	12.2/62	²²
ZnO _{1-x}	Vis.	--	259/1	13.7/15	²³
NH ₂ -terminated SnO ₂	UV-vis	--	2100/0.4	2.5/2.6	²⁴
WO ₃	Vis.	--	400/0.16	20/42	²⁵
GO@TiO ₂	UV-vis	40	0.88/1	0.08/1.5	²⁶
CdS/ZnO	Vis.	5	3.37/1	4E-4/4E-5	²⁷
2D SnS ₂	Vis.	0.464	11/0.05	7.7/-	²⁸
Au@MoS ₂	Vis.	25	~27/10	~2/~2	²⁹
In ₂ O ₃ /Ru(II)	Vis.	--	175000/1	--/-	³⁰
3DOM ZIO	Vis.	50	2160/0.05	1.9/2.1	³¹
Au/WS ₂	Vis.	13.6	~600/1	~1.2/-	³²
SV-MoS ₂ /ZnO	NIR	0.1	226/0.2	1.25/1.85	³³
Black NiO	Vis.	57	19.94/0.18	30/~70	³⁴
a-ZnO	Vis.	--	717/10	2 h/14 h	³⁵
2D MoS ₂	UV-vis	1000	52.1/5	1.5/~1.7	³⁶
SnO ₂ /MoS ₂	Vis.	--	243/3	~5.5/~1.1	³⁷
WO ₃ /CuWO ₄	Vis.	50	8100/1	1.55/0.47	³⁸

0.5 wt% PTCDA/ZnO	Vis.	7.4	10713/1	3.5/2.1	³⁹
Au/SnS ₂	Vis.	--	1100/1	11/9	⁴⁰
Au@MoS ₂ /SnS	Vis.	25	450/1	~4/~4	⁴¹
ZnO nanorods/Pd	Vis.	0.2	160/0.1	0.4/0.5	⁴²
In ₂ O ₃ @ZnO	Vis.	--	180000/5	0.5/1.1	⁴³
MXene/WS ₂	Vis.	100	60/10	0.93/0.88	⁴⁴
BiOI-ZnO	Vis.	0.34	~370/0.1	0.3/0.17	⁴⁵

“--” means cannot extract the information from the article

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